Electronic Supplementary Material (ESI) for Journal of Materials Chemistry C.

Supporting Information

Exploring high temperature templating in non-planar phthalocyanine / copper iodide (111) bilayers

Alexandra J. Ramadan, Luke A. Rochford, Dean S. Keeble, Paul Sullivan, Mary P. Ryan, Tim S. Jones and Sandrine Heutz

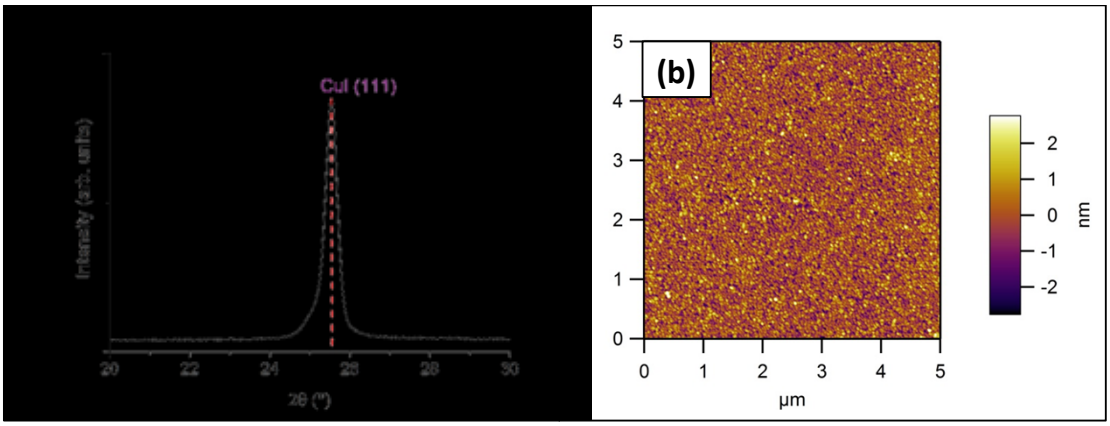

Figure S1. (a) XRD pattern and (b) AFM height image of 30 nm thick film of CuI grown on SiO_2 at T_{sub} = 25°C.

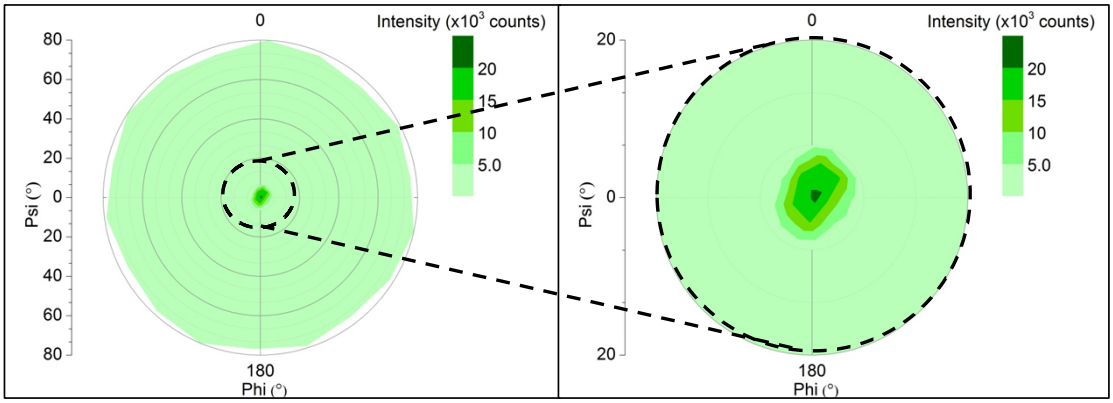

Figure S2. Pole figure of 30 nm thick film of CuI grown on SiO_2 at T_{sub}=155°C. Measurement was carried out on the peak at 2θ = 25.4° corresponding to the (111) diffraction plane.

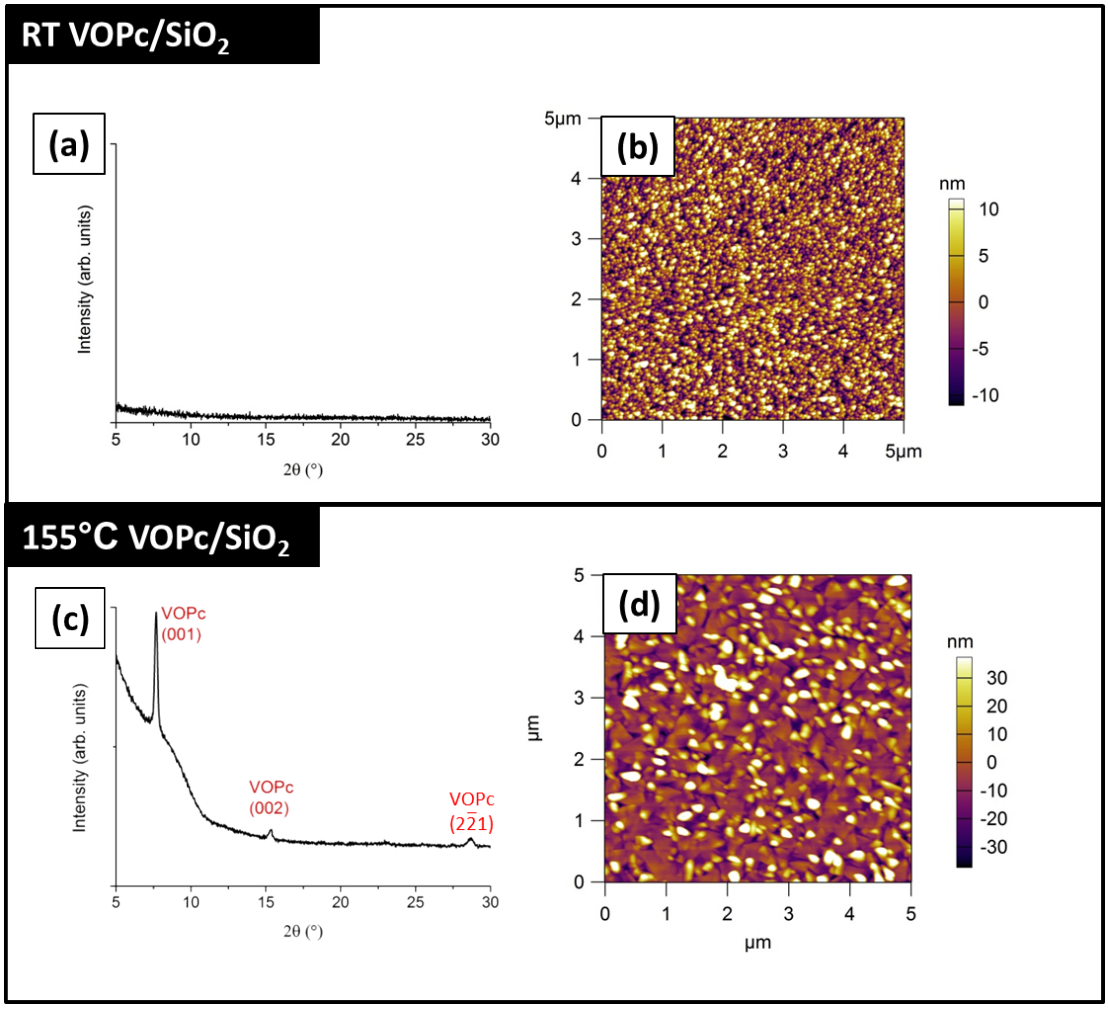

Figure S3. (a) XRD pattern and (b) AFM height image of 50nm thick film of $VOPc/SiO_2$ grown at T_{sub}=25°C. (c) XRD pattern and (b) AFM height image of 50nm thick film of $VOPc/SiO_2$ grown at T_{sub}=155°C.

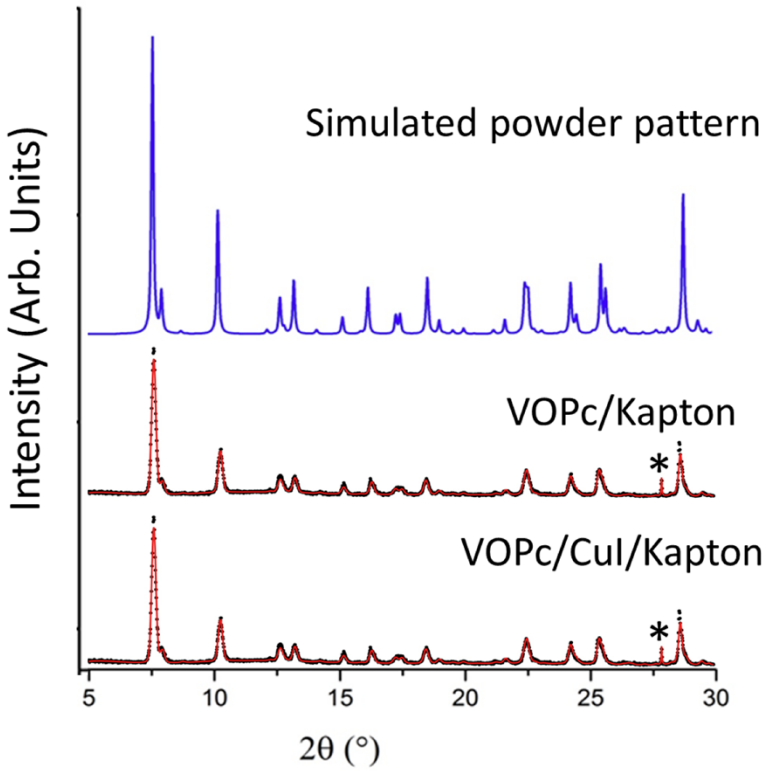

Figure S4. XRD powder pattern comparison of VOPc grown on Kapton and VOPc grown on 30nm CuI/Kapton, showing both the observed data (black dots) and the Rietveld refined fits (red lines). General similarity between the patterns can clearly be observed, and the refinements demonstrate that any subtle differences can be explained by preferred orientation, as discussed in the text. Critically, both powder patterns are consistent with the redetermined single-crystal structure. The simulated powder pattern from the redetermined single-crystal structure has been included in blue to highlight the similarities. The peak labelled * is due to the substrate holder.